

Design strategies towards a small pixel size in a large DMAPS prototype in a 150 nm CMOS process

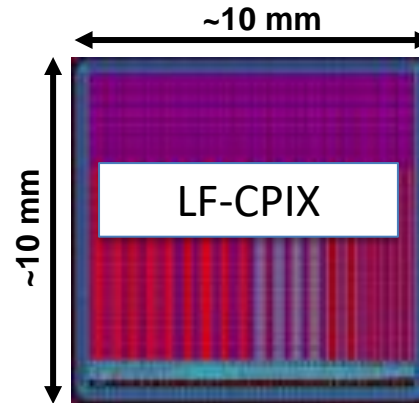
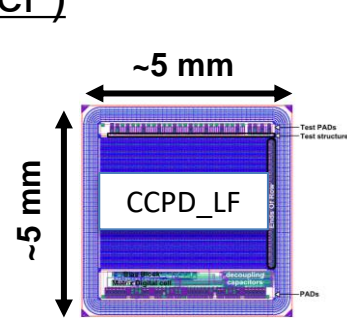
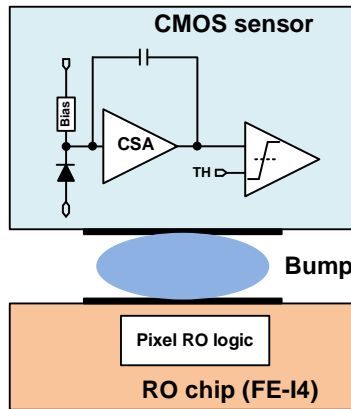
Tianyang Wang

On behalf of Bonn/CPPM/IRFU LFoundry DMAPS development team

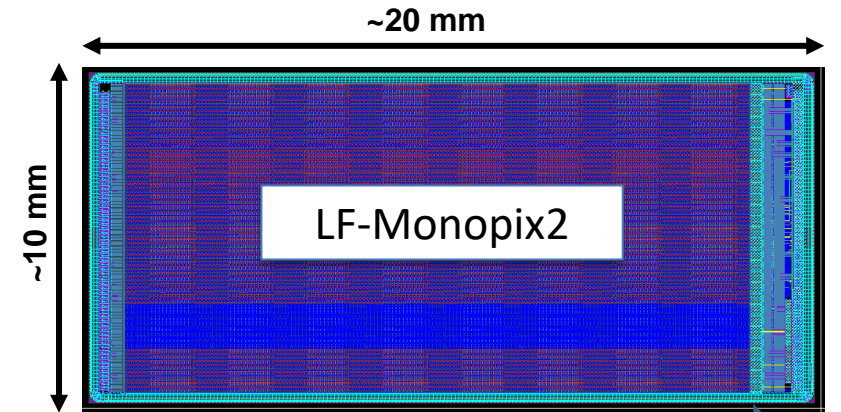
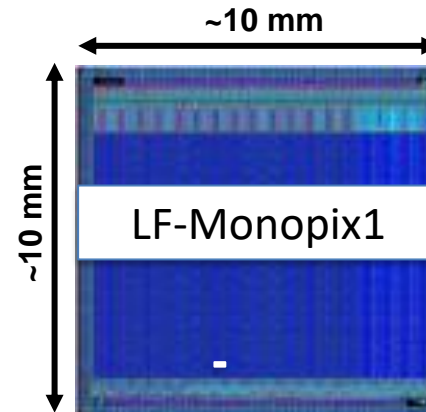
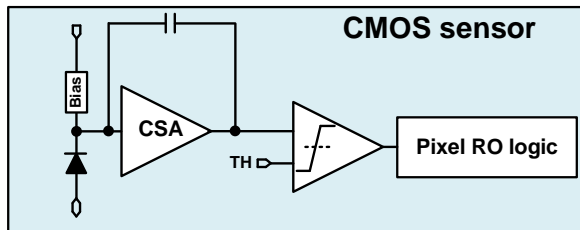
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- Review of LF chips and their design strategy
 - LF-Monopix1 pixel design
 - LF-Monopix2 pixel design
 - Outlook for smaller pixel size
 - Conclusion

LFfoundry DMAPS development line

Hybridized concept (“smart pixel”)



Fully monolithic concept



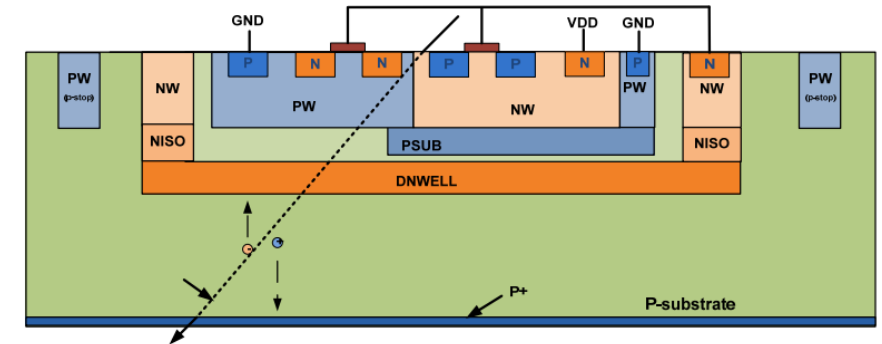
2014

2016

2020

The overall design strategy of LF-Monopix chips

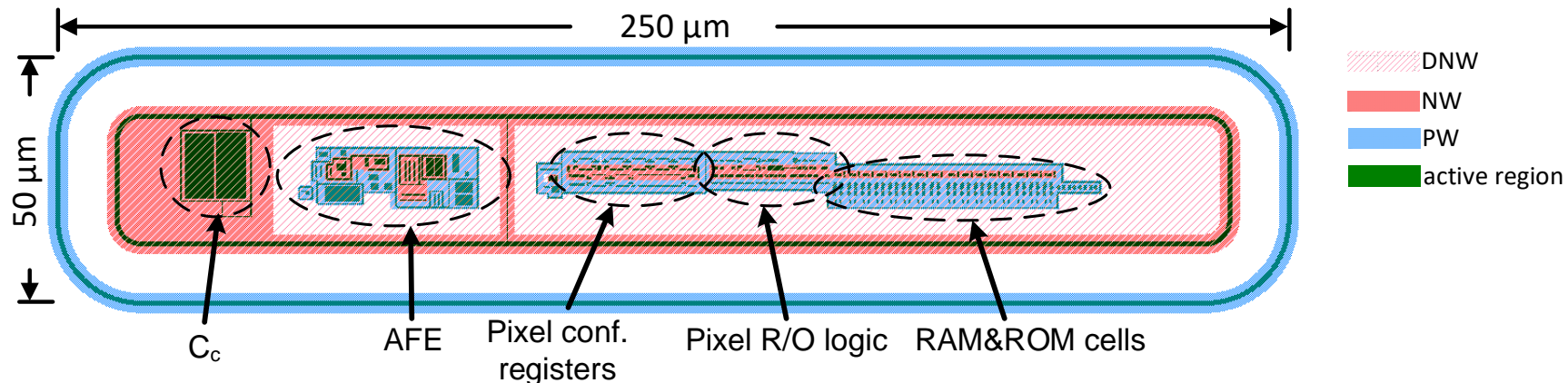
- Inherit the **know-how** from CCPD_LF & LF-CPIX
 - Sensor layout mimicking the standard planar sensor
 - Verified pixel AFE and configuration circuit
- Very **conservative** on circuit design
 - Use well-know and robust circuit structures
 - Very careful shielding scheme
 - Post layout verification is very important
- As a result, robust design has priority over small pixel pitch
 - LF-Monopix1: pixel size is the same as FE-I4 for historical reasons
 - $50\text{ }\mu\text{m} \times 250\text{ }\mu\text{m}$ gives us margin to make some “paranoid” efforts on the pixel design
 - LF-Monopix2: pushing the pixel size to the limit would need too many (new) design changes
 - A conservative choice was made: $50\text{ }\mu\text{m} \times 150\text{ }\mu\text{m}$



LF-Monopix1 pixel design

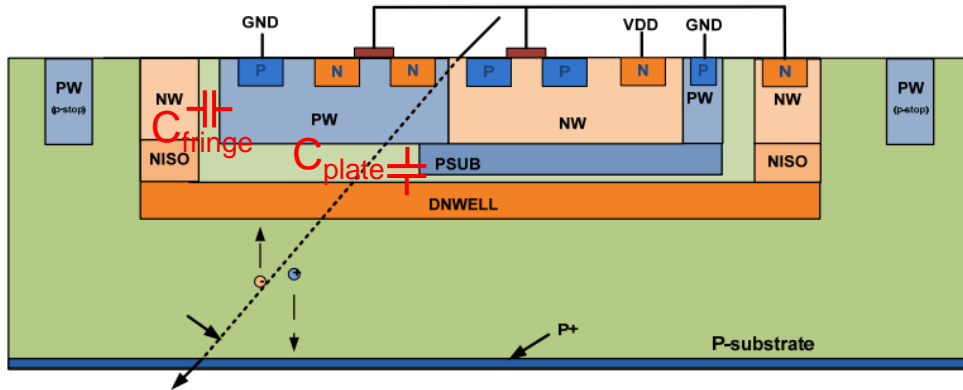
Design considerations: sensor geometry

- Key sensor layout dimensions inherited from previous active and passive pixel chips to avoid surprises on sensor performance (breakdown, charge collection, capacitance, etc.)
 - Width of P-stop (implemented with PWELL)
 - Distance between P-stop and charge collection electrode
 - Over-hang structures above P-stop (not shown in the figure)
- Charge collection electrode is $30\text{ }\mu\text{m} \times 230\text{ }\mu\text{m}$
 - only **~50%** of the total pixel area is available for circuit implementation

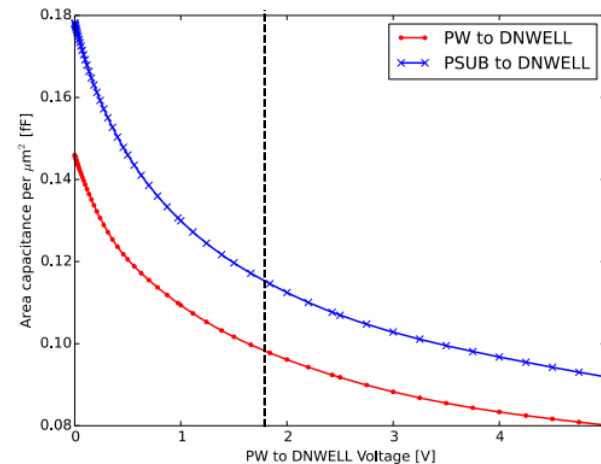


Design considerations: sensor capacitance

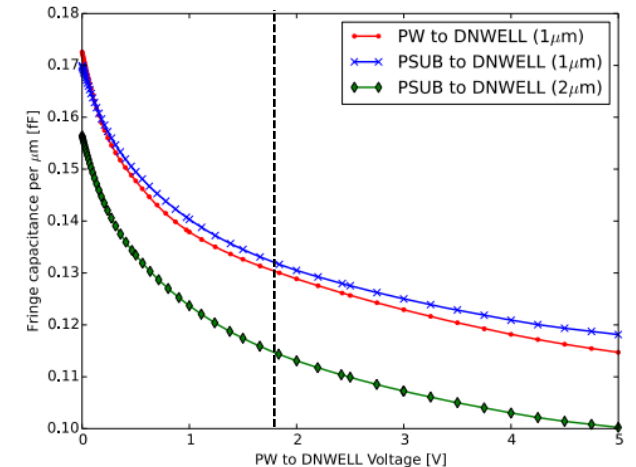
- Capacitance between circuit P-well to the inner wall of charge collection node is not small
 - In-pixel circuit is placed “far away” from vertical N wall
 - Even smaller area “reserved” for circuit if one wants to avoid this fringe capacitance



“Plate” capacitance



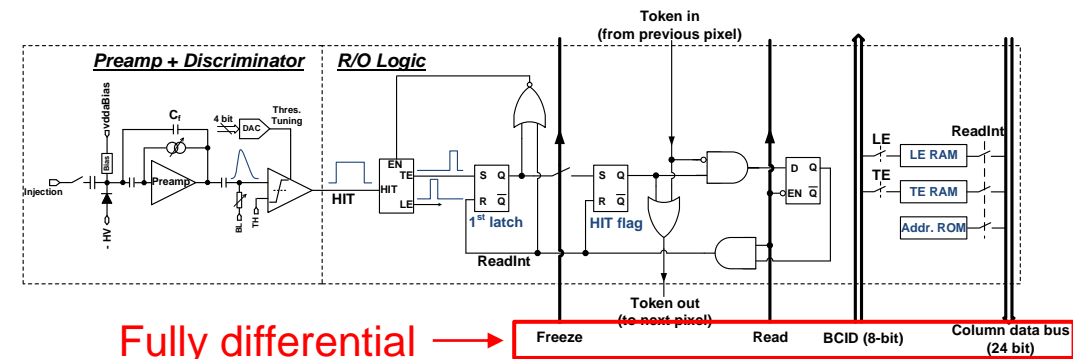
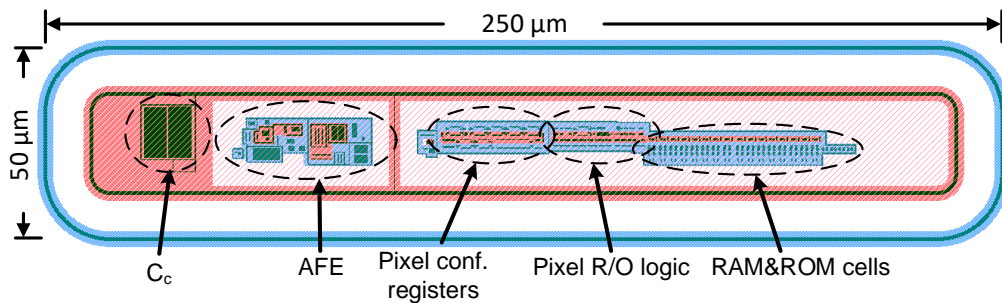
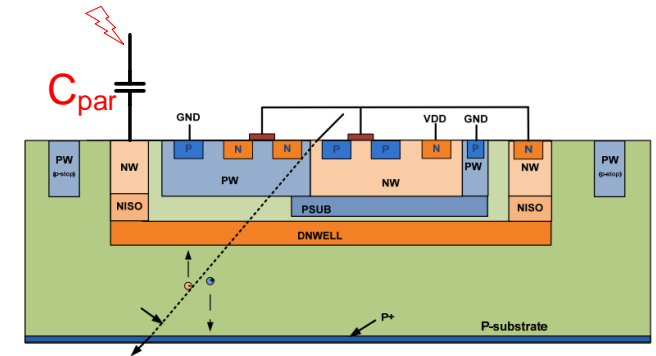
Fringe capacitance



Tomasz Hemperek

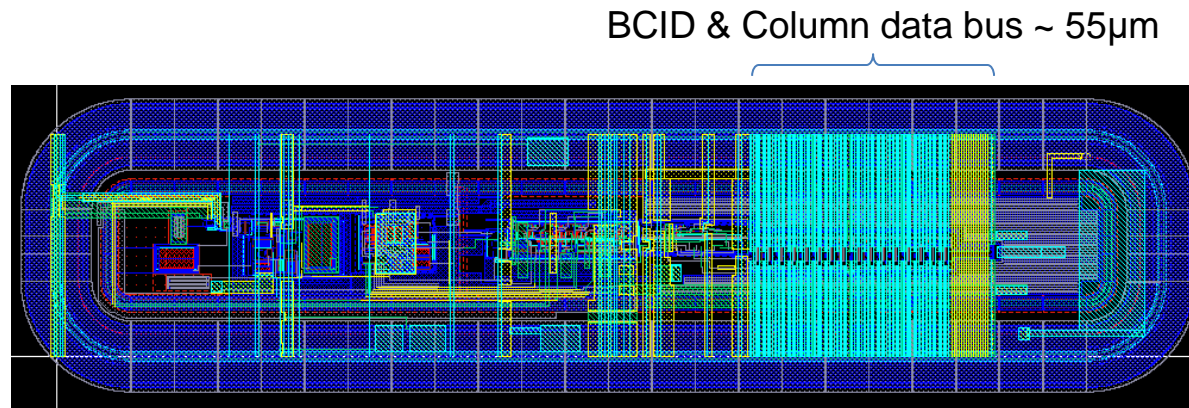
Design considerations: xtalk

- Example: for $C_{\text{par}} = 100 \text{ fF}$, $dV = 1 \text{ mV} \Rightarrow Q_{\text{crosstalk}} = 625 \text{ e}^-$
 - Junction between DNWELL and PWELL/PSUB
 - Minimized circuit area \Rightarrow custom made digital logic
 - Stable gndd \Rightarrow minimize transient current due to digital switching
 - Parasitic from metal routing
 - Good shielding + fully differential signals for data and control lines



Design considerations: metal system

- Extensive shielding especially for digital column signals
 - Shielding layer under signal lines
 - Shielding between two close parallel column signal lines
- Column signal routing takes quite some space



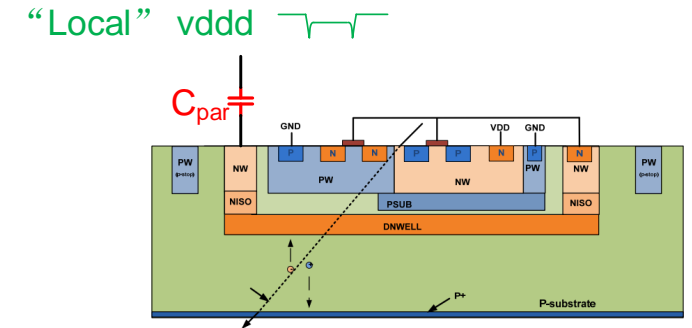
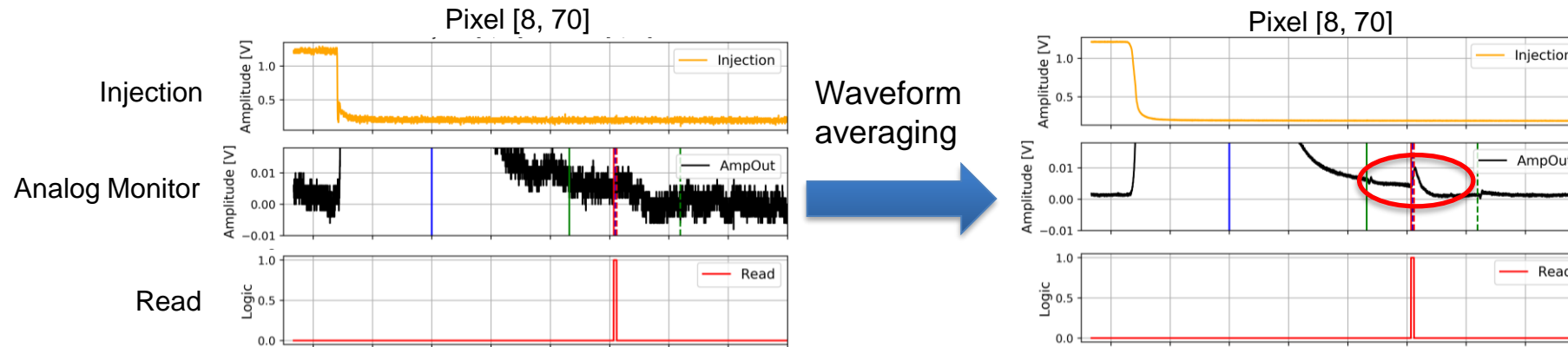
- Local routing: M1 & 2
- Shielding layer: M3 & 4
- Column signal
 - Single-ended: M5
 - Differential: M4 & 5
- PG: MF & MT
 - As wide as possible

Extensive post layout simulation for both pixel and whole column to identify coupling sources

- Column post layout simulation is time consuming and needs proper tool usage
- One can never be too careful

Xtalk measured in LF-Monopix1

- CSA output disturbance in correlation with “Read”
 - “hidden” in the noise floor => visible after “averaging”
 - Due to a flaw in the shielding scheme using vddd

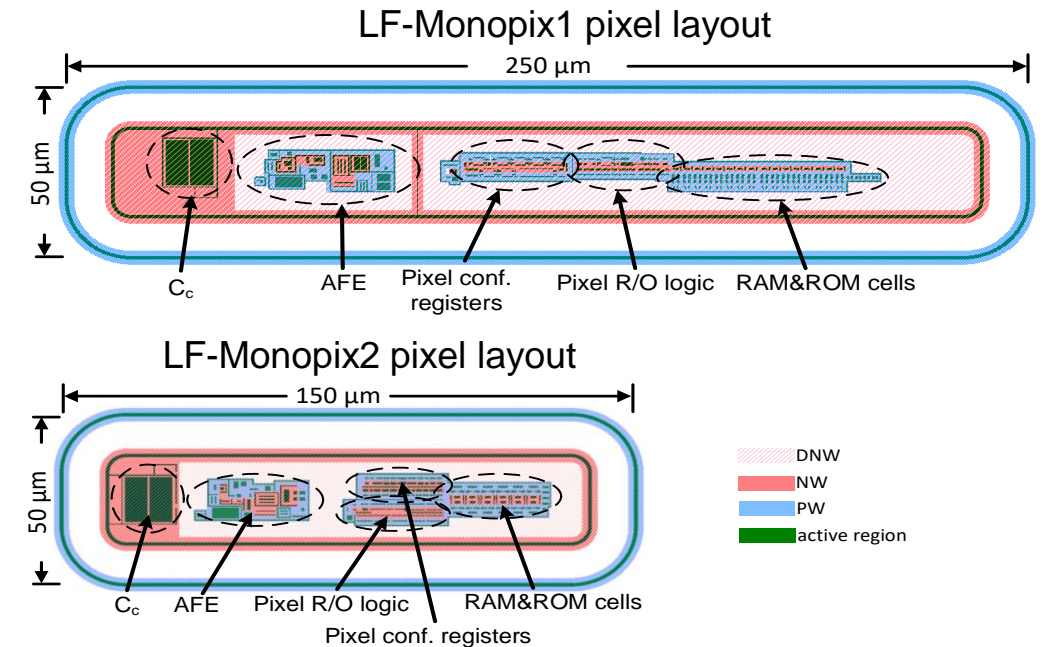


Doubts existed even among ourselves for such a large electrode DMAPS design, but the chip ended up nicely => Prove a good performing large electrode DMAPS chip with complicated pixel circuit for **the first time**

LF-Monopix2 pixel design

LF-Monopix2: towards a smaller pixel

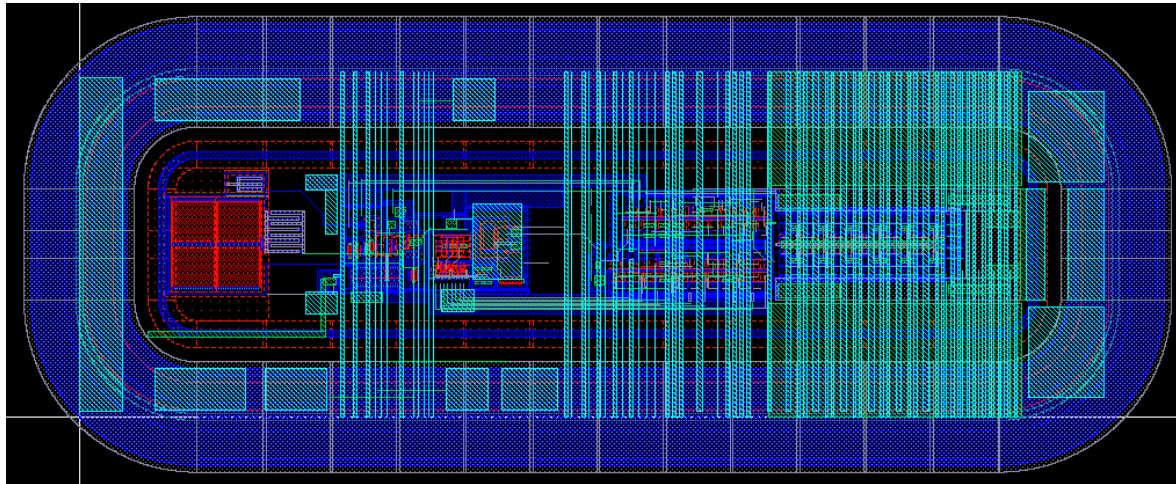
- Key sensor geometries kept the same
 - We did not want to take risks before new possibilities being carefully studied
 - Max. ~50% pixel area for circuit
- Time stamp reduced from 8-bit to 6-bit
 - Should be careful about data loss @ high rate
- Digital logic further optimized for smaller area
 - But only limited improvement could be made



The total circuit area adds up to ~ 1500 μm^2 which defines the ultimate pixel area with the existing circuit design

LF-Monopix2: towards a smaller pixel

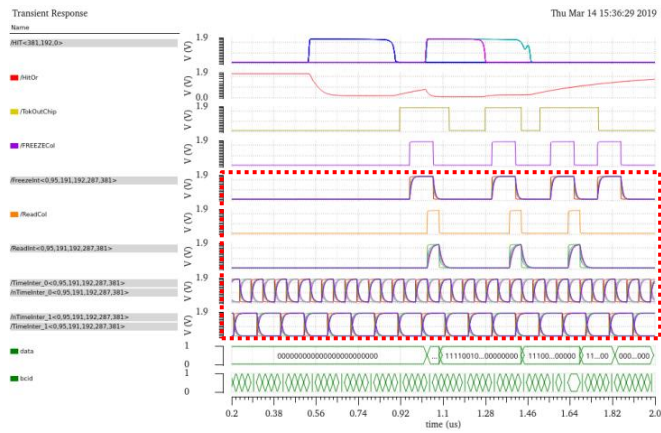
- Remove some overdoing in LF-Monopix1
 - Single-ended signaling used for “Read” & “Freeze” => good shielding suffices
 - No shielding between lines of column data bus => need careful simulation
- Fix the “Read” xtalk in LF-Monopix1
 - Fix was proven effective by measurements



- Local routing: M1 & 2
- Shielding layer: M3 & 4
- Column signal
 - Single-ended: M5
 - Differential: M4 & 5
- PG: MF & MT
 - As wide as possible

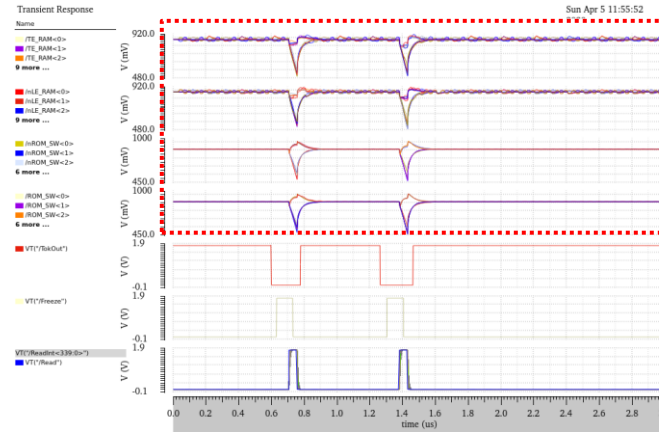
LF-Monopix2: towards a smaller pixel

- Many tedious full column post layout simulation to ensure signal integrity

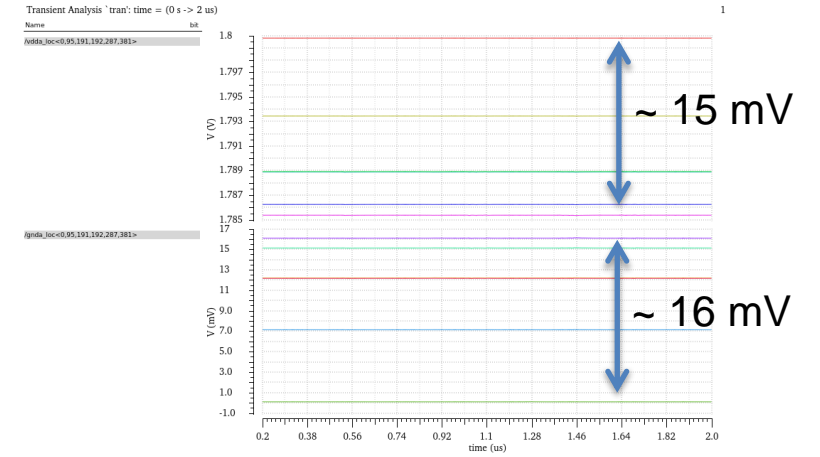


Signal slew & skew along the column

Line width, spacing & shielding



Xtalk and operation speed of column data bus



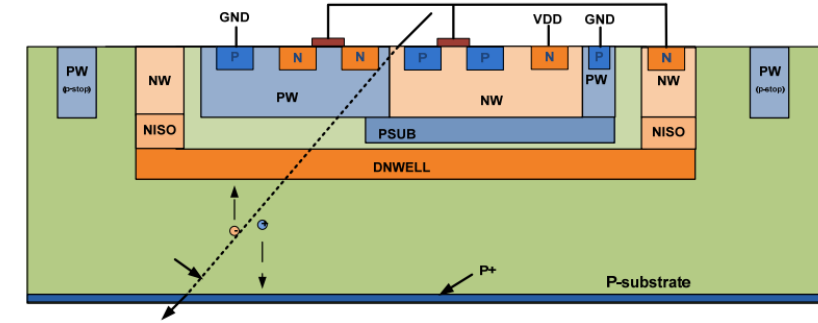
IR of PG along the column

Metal width and layers used for PG

Influence minimum pixel pitch

Outlook to a smaller pixel size

- Squeeze the sensor structure
 - Slimmer P-stop => limited to $1.5\mu\text{m}$ from foundry design rules
 - Smaller gap between charge collection node & P-stop
 - Capacitance to P-stop? [H. Krueger, doi: 10.1088/1748-0221/16/01/P01029](https://doi.org/10.1088/1748-0221/16/01/P01029)
 - Breakdown behavior?
- Smaller gap between N “wall” and circuit P well
 - “Fringe” capacitance
- Column line routing
 - Share lines between two neighboring pixel columns
 - More complex routing within the pixel
 - Larger line load => signal skewing
- Narrower PG metal => IR drop



Conclusions

- LF-Monopix chip series is a nicely performing large electrode DMAPS design
 - Demonstrate large electrode DMAPS with complicated in-pixel circuitry
 - Chip performance verified in large scale matrix
- A smaller pixel ($50\text{ }\mu\text{m} \times 150\text{ }\mu\text{m}$) achieved in LF-Monopix2
 - Not an ultimate small pixel, but a robust pixel with conservative design strategy
 - Performance improvement over LF-Monopix1 verified in measurement
- The ultimate pixel size calls for very careful studies on different aspects
 - May require trade off breakdown, pixel capacitance, xtalk, circuit robustness, etc.